



01-003

April 9, 2004

To: Commissioner for Patents  
P.O.Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/780,416 02/17/04 |

Hsiu-Wen Hsu

METHOD OF FORMING A SEMICONDUCTOR  
DEVICE HAVING A CAPACITOR AND A  
RESISTOR  
| \_\_\_\_\_ |

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on April 12, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

SB Ackerman 4/12/04

U.S. Patent 6,246,084 to Kim, "Method for Fabricating Semiconductor Device Comprising Capacitor and Resistor," describes a method for fabricating a capacitor and resistor over a shallow trench isolation (STI) structure.

U.S. Patent 5,618,749 to Takahashi et al., "Method of Forming a Semiconductor Device Having a Capacitor and a Resistor," describes a method for fabricating a capacitor and resistor over a shallow trench isolation (STI) structure.

U.S. Patent 5,434,098 to Chang, "Double Poly Process with Independently Adjustable Interpoly Dielectric Thickness," describes a capacitor process with an interpoly oxide (IPO) layer.

U.S. Patent 5,656,524 to Eklund et al., "Method of Forming a Polysilicon Resistor Using an Oxide, Nitride Stack," describes a method of forming a polysilicon resistor.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', followed by a large, stylized circular flourish.

Stephen B. Ackerman,  
Reg. No. 37761

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

APR 15 2004

(use several sheets if necessary)

Document Number (Optional)

EP-01-003

Application Number

10/780,416

Applicant

Hsiu-Wen Hsu

Filing Date

02/17/04

Drawn Art Unit

## U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILED DATE IF APPROPRIATE
	6246084	6/12/01	Kim	257	296	11/10/98
	5618749	4/8/97	Takahashi et al.	438	384	3/31/95
	5434098	7/18/95	Chang	437	60	6/3/94
	5656524	8/12/97	Eklund et al.	438	238	6/7/95

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)


EXAMINER

DATE COMPLETED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.